L Number	Hits	Search Text	DB	Time stamp
1	49	("6278124" "4351892" "4544847" "4868395" "4985634"	USPAT	2003/06/25 14:02
		"6344116" "5824437" "5952155" "4377767" "4572956"		
		"5025168" "4385434" "4514638" "5789119" "6011268"		
		"6034376" "4468565" "4525629" "4887282" "5608773"		
		"5627871" "5784150" "6051346" "6225025" "6225025"		
		"4475223" "4902930" "4914304" "5268951" "5377009"		
		"5807648" "5866913" "6040095" "4438336" "4445040"		
		"4532426" "4546260" "4569068" "4590382" "4825087"		
		"4988284" "5582939" "5759724" "5811211" "5831274"		
		"5834783" "5892231" "5935735" "5973332" "6090528").pn.		

Most Frequently Occurring Classifications of Patents Returned From A Search of 09993500 on March 29, 2002

Original Classifications

- 8 430/5
- 7 250/492.2
- 5 378/34
- 5 430/296
- 4 250/398
- 3 250/491.1
- 3 250/492.22
- 2 250/396ML
- 2 250/492.23
- 2 430/30

Cross-Reference Classifications

- 5 250/398
- 5 250/492.2
- 5 430/296
- 4 250/491.1
- 4 430/30
- 2 250/396MIL
- 2 250/396R
- 2 250/492.3
- 2 250/505.1
- 2 378/208
- 2 430/311
 - 2 430/322
 - 2 430/5
 - 2 438/975

Combined Classifications

- 12 250/492.2
- 10 430/296
- 10 430/5
- 9 250/398
- 7 250/491.1
- 6 378/34
- 6 430/30
- 4 250/396MIL
- 4 250/492.22
- 3 250/492.23
- 2 250/396R
- 2 250/492.3
- 2 250/505.1

- 2 355/53
- 2 356/401
- 2 378/208
- 2 430/311
- 2 430/322
- 2 438/975

itles of Most Frequently Occurring Classifications of Patents Returned From A Search of 09993500 on March 29, 2002

12 250/492.2 (7 OR, 5 XR)

Class 250: RADIANT ENERGY

250/492.1 IRRADIATION OF OBJECTS OR MATERIAL

250/492.2 .Irradiation of semiconductor devices

10 430/296 (5 OR, 5 XR)

Class 430: RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF

430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF

RADIATION SENSITIVE MATERIAL, OR PRODUCING

NONPLANAR OR

PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

430/296 .Electron beam imaging

10 430/5 (8 OR, 2 XR)

Class 430: RADIATION IMAGERY CHEMISTRY: PROCESS,

COMPOSITION, OR PRODUCT THEREOF

430/4 RADIATION MODIFYING PRODUCT OR PROCESS OF

MAKING

430/5 Radiation mask

9 250/398 (4 OR, 5 XR)

Class 250: RADIANT ENERGY

250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR

FOCUSSING

250/398 .With target means

7 250/491.1 (3 OR, 4 XR)

Class 250: RADIANT ENERGY

250/491.1 MEANS TO ALIGN OR POSITION AN OBJECT RELATIVE

TO A SOURCE OR DETECTOR

6 378/34 (5 OR, 1 XR)

Class 378: X-RAY OR GAMMA RAY SYSTEMS OR DEVICES

378/1 SPECIFIC APPLICATION

378/34 .Lithography

6 430/30 (2 OR, 4 XR)

Class 430: RADIATION IMAGERY CHEMISTRY: PROCESS,

COMPOSITION, OR PRODUCT THEREOF

430/30 INCLUDING CONTROL FEATURE RESPONSIVE TO A TEST OR MEASUREMENT

4 250/396ML (2 OR, 2 XR)

Class 250: RADIANT ENERGY

250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR

FOCUSSING

250/396ML . Magnetic lens

4 250/492.22 (3 OR, 1 XR)

Class 250: RADIANT ENERGY

250/492.1 IRRADIATION OF OBJECTS OR MATERIAL

250/492.2 Irradiation of semiconductor devices

250/492.22 ...Pattern control

3 250/492.23 (2 OR, 1 XR)

Class 250: RADIANT ENERGY

250/492.1 IRRADIATION OF OBJECTS OR MATERIAL

250/492.2 .Irradiation of semiconductor devices

250/492.23 ... Variable beam

2 250/396R (0 OR, 2 XR)

Class 250: RADIANT ENERGY

250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR FOCUSSING

2 250/492.3 (0 OR, 2 XR)

Class 250: RADIANT ENERGY

250/492.1 IRRADIATION OF OBJECTS OR MATERIAL

250/492.3 .Ion or electron beam irradiation

2 250/505.1 (0 OR, 2 XR)

Class 250: RADIANT ENERGY

250/505.1 RADIATION CONTROLLING MEANS

2 355/53 (1 OR, 1 XR)

Class 355: PHOTOCOPYING

355/18 PROJECTION PRINTING AND COPYING CAMERAS

355/53 Step and repeat

2 356/401 (1 OR, 1 XR)

Class 356: OPTICS: MEASURING AND TESTING

356/399 BY ALIGNMENT IN LATERAL DIRECTION 356/401 With registration indicia (e.g., scale) (0 OR, 2 XR) 2 378/208 Class 378: X-RAY OR GAMMA RAY SYSTEMS OR DEVICES 378/204 **ACCESSORY** 378/208 Object holder or support 2 430/311 (0 OR, 2 XR)Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF 430/269 **IMAGING AFFECTING PHYSICAL PROPERTY OF** RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

2 430/322 (0 OR, 2 XR)

Class 430: RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF

.Making electrical device

430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF RADIATION SENSITIVE MATERIAL, OR PRODUCING

NONPLANAR OR

430/311

PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/322 .Forming nonplanar surface

2 438/975 (0 OR, 2 XR)

Class 438: SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/975 SUBSTRATE OR MASK ALIGNING FEATURE LUS Search Results for S/N 09993500, Searched March 29, 2002

6278124

4572956 5025168

4385434

4514638

5789119